

MULTIVARIABLE SOLVER FOR OPTICAL PROXIMITY CORRECTION

ABSTRACT

The method of the invention tracks how the collective movement of edge segments in a mask layout alters the resist image values at control points in the layout and simultaneously determines a correction amount for each edge segment in the layout. A multisolver matrix that represents the collective effect of movements of each edge segment in the mask layout is used to simultaneously determine the correction amount for each edge segment in the mask layout.

[Fig. 6]